

L42 ANSWER 15 OF 29 WPIX COPYRIGHT 2003 THOMSON DERWENT on SIN
 AN 1998-156322 [14] WPIX
 DNN N1998-124947 DNC C1998-050336
 TI CMOS device - has gate **insulating** film formed over substrate,
 over which **germanium electrode layer** is
 formed.
 DC L03 U11 U13
 PA (SONY) SONY CORP
 CYC 1
 PI JP 10027854 A 19980127 (199814)* 6p H01L021-8238
 ADT JP 10027854 A JP 1996-180919 19960710
 PRAI JP 1996-180919 19960710
 IC ICM H01L021-8238
 ICS H01L021-336; H01L027-092; H01L029-78
 AB JP 10027854 A UPAB: 19980410
 The device has a semiconductor substrate on which a gate
insulating film (23) is formed. A **germanium**
electrode layer (31) is formed on the gate insulating
 layer.
 ADVANTAGE - Enables production of surface channel type PMOS and NMOS
 using single polar gate electrode.
 Dwg.1/6
 FS CPI EPI
 FA AB: G1
 MC CPI: L04-C11C
 EPI: U11-C05F1; U13-D02A

6/9/9 (Item 9 from file: 350)
 DIALOG(R)File 350:Derwent WPIX
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010404683 **Image available**

WPI Acc No: 1995-305997/199540

XRAM Acc No: C95-136432

XRPX Acc No: N95-232143

Semiconductor device e.g. MOST for LSI circuit - has double layered structure of gate electrode, consisting of polycrystalline silicon film and germanium film, formed over gate insulating film

Patent Assignee: TOSHIBA KK (TOKYO)

Number of Countries: 001 Number of Patents: 001

Patent Family:

Patent No	Kind	Date	Applicat No	Kind	Date	Week
JP 7202178	A	19950804	JP 93351053	A	19931228	199540 B

Priority Applications (No Type Date): JP 93351053 A 19931228

Patent Details:

Patent No Kind Lan Pg Main IPC Filing Notes

JP 7202178 A 12 H01L-029/78

Abstract (Basic): JP 7202178 A

The semiconductor device has a silicon substrate (11) on which a gate insulating film (12) is formed. The thickness of the insulating film is about 70nm thickness. A polycrystalline silicon film (13a) of 50nm thickness is formed over the insulating film by chemical deposition method. A polycrystalline germanium film (13b) of 0.3 micrometer thickness is grown externally by the low voltage chemical deposition method. The germanium film is formed over the silicon film and forms a gate electrode (13) by plasma etching.

ADVANTAGE - Ensures less power. Reduces impurity density of substrate sustains predetermined threshold voltage.

Dwg.1/12

Title Terms: SEMICONDUCTOR; DEVICE; LSI; CIRCUIT; DOUBLE; LAYER; STRUCTURE;

L42 ANSWER 21 OF 29 WPIX COPYRIGHT 2003 THOMSON DERWENT on STN
 AN 1993-328086 [41] WPIX
 CR 1992-131697 [16]
 DNC C1993-145153
 TI Deposition of **germanium thin films** on silicon di
 oxide - using interposed thin film of polycrystalline silicon as
 support in the fabrication of self-aligned MOS structures.
 DC L03
 IN OZTURK, M; WORTMAN, J
 PA (UYNC-N) UNIV NORTH CAROLINA STATE
 CYC 1
 DT US 5250452 A 19931005 (199341)* 7p H01L021-441
 ADT US 5250452 A Div ex US 1990-515595 19900427, US 1991-717631 19910619
 PDT US 5250452 A Div ex US 5101247
 PRAI US 1990-515595 19900427; US 1991-717631 19910619
 IC ICM H01L021-441
 AB US 5250452 A UPAB: 19931130
 Depositing polycrystalline **Ge films** on **SiO2**
 comprises: depositing a layer of polycrystalline Si on a SiO2 layer, thick
 enough to support the deposition of polycrystalline Ge on it, while thin
 enough to be deposited sufficiently rapidly to substantially avoid
 deleterious effects on the characteristics of the oxide structure during
 the deposition process; exposing the polycrystalline Si layer to a
 Ge-contg. gas at a temp. below that at which Ge will deposit on
 SiO2 alone while preventing native growth of SiO2 on the
 polycrystalline Si layer, and for a time sufficient to deposit a layer of
 polycrystalline Ge upon the polycrystalline Si that is thick enough to
 mask the polycrystalline Si layer and underlying SiO2 layer from ion
 implantation.
 USE/ADVANTAGE - Method of using **Ge thin films** in
 combination with **SiO2** in the fabrication of self-aligned MOS
 structures, with the advantage of working with a low thermal budget.
 Dwg.1,2/3
 FS CFI

L121 ANSWER 4 OF 8 HCAPLUS COPYRIGHT 2003 ACS ON STN

AN 2000 600624 HCAPLUS

DN 133 201730

TI Fabrication of semiconductor devices provided with depletion-decreased gate electrodes in MIS FETs

IN Mokami, Toru

PA Nec Corp., Japan

SO Jpn. Kokai Tokkyo Koho, 10 pp.

CODEN: JKXXAP

DT Patent

LA Japanese

IC ICM H01L021-8238

ICS H01L027-092; H01L029-43; H01L029-78

CC 76-3 (Electric Phenomena)

FAN. CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000236028	A2	20000829	JP 1999-37200	19990216
JP 3261697	B2	20020304		
PRAI JP 1999-37200		19990216		

AB The title fabrication involves (1) forming a gate insulator film on a component-isolated semiconductor substrate, (2) depositing a semiconductor film in doping a 1st cond.-type dopant according to the cond. for gate electrode as a 1st electrode formed on the gate insulator film, (3) depositing a conductor film without doping in formation of a gate electrode as a 2nd electrode film over the 1st electrode film, (4) doping a 2nd cond.-type dopant in prepn. of a 2nd cond.-type gate electrodes in the semiconductor device, (5) etching to pattern the 1st and 2nd gate electrodes, and (6) doping in prepn. of source/drain regions in the semiconductor devices. The process provides the semiconductor devices with depletion-decreased gate electrodes in MIS FETs.

IT 7440-21-3P, Polysilicon, properties 7440-56-4P, Germanium, Properties
 RL: DEV (Device component use); PNU (Preparation, unclassified); PRP (Properties); PREP (Preparation); USES (Uses)
 (gate electrode; fabrication of semiconductor devices provided with depletion-decreased gate electrodes in MIS FETs)

IT 7440-56-4P, Germanium, properties
 RL: DEV (Device component use); PNU (Preparation, unclassified); PRP (Properties); PREP (Preparation); USES (Uses)
 (gate electrode; fabrication of semiconductor devices provided with depletion-decreased gate electrodes in MIS FETs)

RN 7440-56-4 HCAPLUS

CN Germanium (7CI, 8CI, 9CI) (CA INDEX NAME)

Ge

JP priority 2/16/99
 JP pub date 8/29/00

L57 ANSWER 1 OF 1 WPIX COPYRIGHT 2003 THOMSON DERWENT on STN
 AN 2000-590915 [56] WPIX
 DNN N2000-437439 DMC C2000-176756
 TI Semiconductor device manufacturing method involves doping predetermined
 impurities on gate electrode areas of different polarities.
 DC L03 U11 U12
 PA (NIDE) NEC CORP
 CYC 1
 PI JP 2000236028 A 20000829 (200056)* 10p H01L021-8238
 ADT JP 2000236028 A JP 1999-37200 19990216
 PRA1 JP 1999-37200 19990216
 IC ICM H01L021-8238
 ICS H01L027-092; H01L029-43; H01L029-78
 AB JP2000236028 A UPAB: 20001106
 NOVELTY - A gate insulating film is formed on the silicon substrate (10).
 The doping of predetermined impurities is performed to the gate electrode
 (61,62) areas of different electric polarities, which is provided on the
 respective electrode formation films
 USE - For manufacturing of semiconductor device such as MIS type
 field effect transistor.
 ADVANTAGE - The impurity is doped during film formation and doping is
 performed at high concentration. The degradation of transistor capability
 is reduced.
 DESCRIPTION OF DRAWING(S) - The figure shows the sectional view of
 semiconductor device manufacturing method.
 Silicon substrate 10
 Gate electrodes 61,62
 Dwg. 1/6
 FS CPI EPI

L24 ANSWER 15 OF 21 CAPLUS COPYRIGHT 2003 ACS on STN
 AN 1999:162136 CAPLUS
 DN 130:176398
 TI Germanium cold cathode electron sources and fabrication thereof
 IN Kobayashi, Takeshi
 PA Shinko Electric Industries Co., Ltd., Japan
 SO Jpn. Kokai Tokkyo Koho, 5 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 IC ICM H01J001-30
 ICS H01J009-02; H01L029-66
 CC 76-12 (Electric Phenomena)
 Section cross-reference(s): 56

FAN CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 11067059	A2	19990309	JP 1997-222253	19970819
PRAI	JP 1997-222253		19970819		
AB	The title cold cathodes comprise a Ge emitter electrode and a Ge gate electrode in adjacent positions each other formed over an insulator layer on a substrate, wherein an Al film is provided between the Ge electrode layers and the insulator layer so as to make Al diffused into the Ge electrode in forming an Al-doped Ge p-semiconductor by annealing. The Al-doped Ge p-semiconductor gives the cold cathodes better electron emission efficiency and increased lifetime.				
IT	7440-56-4P, Germanium, properties RL: DEV (Device component use); PEP (Physical, engineering or chemical process); PNU (Preparation, unclassified); PRP (Properties); PREP (Preparation); PROC (Process); USES (Uses) (Al-doped, p-semiconductor cold cathode; germanium cold cathode electron sources and fabrication thereof)				
RN	7440-56-4 CAPLUS				
CN	Germanium (7CI, 8CI, 9CI) (CA INDEX NAME)				

Ge

IT 7429-90-5, Aluminum, uses
 RL: MOA (Modifier or additive use); USES (Uses)
 (dopant, for annealing; germanium cold cathode electron sources and fabrication thereof)
 RN 7429-90-5 CAPLUS
 CN Aluminum (8CI, 9CI) (CA INDEX NAME)

Al

L24 ANSWER 16 OF 21 CAPLUS COPYRIGHT 2003 ACS ON STN
 AN 1996:644986 CAPLUS
 DN 125:343262
 TI Controlled grain size and location of Ge thin films on
 silicon dioxide by low temperature selective solid phase
 crystallization
 AU Yang, C. M.; Atwater, Harry A.
 CS Thomas J. Watson Lab. Applied Physics, California Inst. Technol.,
 Pasadena, CA, 91125, USA
 SO Materials Research Society Symposium Proceedings (1996),
 403(Polycrystalline Thin Films: Structure, Texture, Properties, and
 Applications II), 113-118
 CODEN: MRSPDH, ISSN: 0272-9172
 PB Materials Research Society
 DT Journal
 LA English
 CC 75-1 (Crystallography and Liquid Crystals)
 AB Selective solid phase crystn. for control of grain size and location in
 polycryst. thin Ge films on amorphous SiO2
 substrates is described. The approach consists of selective solid phase
 crystal nucleation via an alloy reaction at predefined nucleation sites,
 which consist of metal islands deposited on top of the amorphous
 Ge film, followed by lateral solid phase epitaxial
 growth. Grain sizes as large as 30 μm were achieved in 50 nm thick
 Ge films at <475 degree. B and P doping resulted in
 significant lateral solid-phase epitaxial growth rate enhancements.
 IT 7440-56-4, Germanium, processes
 RL: PEP (Physical, engineering or chemical process); PROC (Process)
 (controlled grain size and location of Ge thin films
 on silicon dioxide by low temp. selective solid phase
 crystn.)
 RN 7440-56-4 CAPLUS
 CN Germanium (7CI, 8CI, 9CI) (CA INDEX NAME)

Ge

IT 7440-42-8, Boron, processes
 RL: MOA (Modifier or additive use); PEP (Physical, engineering
 or chemical process); PROC (Process); USES (Uses)
 (solid-phase epitaxy of boron-doped germanium on silica)
 RN 7440-42-8 CAPLUS
 CN Boron (8CI, 9CI) (CA INDEX NAME)

B

L103 ANSWER 15 OF 24 HCAPLUS COPYRIGHT 2003 ACS on STN

AN 1995:808348 HCAPLUS

DN 123:244385

TI Semiconductor device having germanium-silicon mixed crystal source-drain regions and its manufacture

IN Ando, Takeshi

PA Nippon Electric Co, Japan

SO Jpn. Kokai Tokkyo Koho, 5 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

IC ICM H01L029-78

CC 76-3 (Electric Phenomena)

PAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
FI	JP 07169958	A2	19950704	JP 1993-317009	19931216
PRAI	JP 1993-317009		19931216		

AB The device has a Si substrate where a x-type (x = elec. cond. type) 1st surface region successively coated with a gate-insulating film and a gate electrode is sandwiched with a 2nd and a 3rd surface regions resp. coated with y-type (x. noteq. y) source and drain regions consisting of Ge or Ge-Si mixed crystal semiconductor layers. The title manuf. involves growth of the semiconductor layer on the 2nd and the 3rd regions on the substrate by selective CVD, followed by implantation of a y-type dopant to form the source and drain regions. The method is useful for manuf. of CMOS and gave transistors with shallow junction.

IT 7631-86-9, Silicon oxide, processes
 RL: DEV (Device component use); PEP (Physical, engineering or chemical process); PROC (Process); USES (Uses)
 (gate-insulating film; manuf. of semiconductor device having germanium-silicon mixed crystal source-drain regions)

IT 7440-21-3, Silicon, processes 7440-56-4, Germanium, processes 11148-21-3
 RL: DEV (Device component use); PEP (Physical, engineering or chemical process); PROC (Process); USES (Uses)
 (manuf. of semiconductor device having germanium-silicon mixed crystal source-drain regions)

L55 ANSWER 1 OF 1 WPIX COPYRIGHT 2003 THOMSON DERWENT on STN
 AN 1995-267403 [35] WPIX
 DNN N1995-205406 DNC C1995-121530
 TI Structure of MOSFET - provides source and drain domains of N type
 conductivity on second and third surface domains of P type conductivity.
 DC L03 U12
 PA (NIDE) NEC CORP
 CYC 1
 PI JP 07169958 A 19950704 (199535)* 5p H01L029-78 <--
 ADT JP 07169958 A JP 1993-317009 19931216
 PRAI JP 1993-317009 19931216
 IC JCM H01L029-78
 AB JP 07169958 A UPAB: 19950905
 The MOSFET consists of a first surface domain (31) between a second
 surface domain (32) and a third surface domain (33) at surface of P type
 Si surface (1). A gate electrode (3) is provided through gate oxide film
 (2) on the first surface domain of P type conductivity.
 A silicon oxide film (4) covers the whole gate electrode thereby
 creating side walls (5). The source and drain domains (10) are formed on
 the second and third surface domains of P type conductivity. The source
 and drain domains are composed of N type silicon layer (6) and N type
 Germanium layer (7).
 ADVANTAGE - Provides shallow junction with sufficient control.
 Dwg.1/5
 CPI EPI

LI03 ANSWER 21 OF 24 HCAPLUS COPYRIGHT 2003 ACS on STN

AN 1986-617398 HCAPLUS
 DN 105:217398
 TI Complementary field-effect transistors
 IN Mori, Kazutaka; Murata, Jun
 PA Hitachi, Ltd., Japan
 SO Jpn. Kokai Tokkyo Koho, 4 pp.
 CODEN: JKXXAF

DT Patent
 LA Japanese

IC ICM H01L027-08
 ICS H01L021-20; H01L029-78
 CC 76-3 (Electric Phenomena)

Section cross-reference(s): 75
 FAN: CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 61112364	A2	19860530	JP 1984-233106	19841107
PRAI	JP 1984-233106		19841107		

AB In a complementary MIS FET having n and a p-type MIS FETs in which a gate insulator and a gate electrode are formed on p- and n-type regions, resp., p-Si and n-Ge are used for the p- and n-type regions, resp. Thus, after a p-type well region with n-type source and drain regions was formed in an n-Si substrate, n-Ge was epitaxially grown close to the p-type well region, and p-type source and drain regions were formed in the n-Ge by diffusion of Ga or In. A MOS FET produced had equal channel conductances with a high hole mobility and no latch-up.

IT 7440-56-4, properties
 RL: PRP (Properties)
 (epitaxy of, in complementary MIS FET manuf.)
 RN 7440-56-4 HCAPLUS
 CN Germanium (7CI, 8CI, 9CI) (CA INDEX NAME)

Ge

IT 7440-74-6, uses and miscellaneous
 RL: USBS (Uses)
 (source-drain region formation in germanium doped with, in complementary FET manuf.)
 RN 7440-74-6 HCAPLUS
 CN Indium (8CI, 9CI) (CA INDEX NAME)

In

L106 ANSWER 13 OF 13 HCAPLUS COPYRIGHT 2003 ACS on STN

AN 1984:113359 HCAPLUS

DN 100:113359

TI Thin-film MOSFET

PA Toshiba Corp., Japan

SO Jpn. Kokai Tokkyo Koho, 4 pp.

CODEN: JKKXAF

DT Patent

LA Japanese

IC H01L021-84; H01L021-324; H01L029-78

CC 76-3 (Electric Phenomena)

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 58186950	A2	19831101	JP 1982-68845	19820426
	JP 03073149	B4	19911120		

PRAL JP 1982-68845 19820426

AB Thin-film MOSFETs with good threshold voltages and mobilities of .apprx.20

cm²/V.s are fabricated by depositing a film (e.g., Ge)

with a large IR absorption on glass, depositing amorphous or polycryst.

Si, masking with SiO₂, exposing to IR radiation to crystallize the film,

implanting P ions in the source and drain regions, and

forming the contacts.

IT 7440-56-4, uses and miscellaneous

RL: TEM (Technical or engineered material use); USES (Uses)

(IR absorber, for IR crystn. of polysilicon films for transistors)

RN 7440-56-4 HCAPLUS

CN Germanium (7CI, 8CI, 9CI) (CA INDEX NAME)

Ge

IT 7440-21-3, properties

RL: PRP (Properties); TEM (Technical or engineered material use); USES

(Uses)

(IR crystn. of polycryst., on germanium films)

RN 7440-21-3 HCAPLUS

CN Silicon (7CI, 8CI, 9CI) (CA INDEX NAME)

Si

IT 7631-86-9, uses and miscellaneous

RL: USES (Uses)

(mask, for polysilicon crystn. in transistor fabrication)

RN 7631-86-9 HCAPLUS

CN Silica (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)

O=Si=O

114 ANSWER 3 OF 4 HCAPLUS COPYRIGHT 2003 ACS on STN

AN 1980:119708 HCAPLUS

DN 92:119708

TI Electrophotographic plates

IN Komatsu, Toshiyuki; Hirai, Hiroshi; Nakagawa, Katsumi; Fukuda, Chuji

PA Canon K. K., Japan

SO Jpn. Kokai Tokkyo Koho, 20 pp.

CODEN: JKKXAF

DT Patent

LA Japanese

IC G03G005-08; G03G005-04

CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic Processes)

FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 54145541	A2	19791113	JP 1978-53607	19780504
	JP 61061104	B4	19861224		

PRAI JP 1978-53607

AB Electrophotog. plates contain an amorphous Ge layer having homojunction type depletion layer as the photoconductor layer, and a transparent surface layer. The depletion layer acts as the charge carrier-generating layer. The electrophotog. plate may also have a barrier layer and also an elec. insulating top layer. The homojunction may be a p-n, i-p, or i-n junction. The electrophotog. plates exhibit excellent sensitivity, and give copies with high resolu., high optical d., and good halftone reproducibility. Thus, amorphous Ge is deposited on a glass support having a transparent In2O3 conductor layer by using chem. vapor deposition from GeH4; then B-doped Ge is deposited from a GeH4-B2H6 mixt., and the Ge layer is overcoated with a polycarbonate resin to give an electrophotog. plate. The electrophotog. plate gave copies with high resolu. and good halftone reproducibility.

L121 ANSWER 7 OF 8 HCAPLUS COPYRIGHT 2003 ACS ON STN
 AN 1994:546817 HCAPLUS
 DN 121:146817
 TI Manufacture of semiconductor device with low strain
 IN Tanho, Toshiharu
 PA Matsushita Electronics Corp, Japan
 SO Jpn. Kokai Tokkyo Koho, 4 pp.
 CODEN: JKKXAF
 DT Patent
 LA Japanese
 IC ICM H01L021-338
 ICS H01L029-812, H01L021-28
 CC 76-3 (Electric Phenomena)
 FAN CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 06069243	A2	19940311	JP 1992-221075	19920820

PRAI JP 1992-221075 19920820
 AB The title device is manufd. by a process including following successive steps: (1) forming the 1st conductive semiconductor layer on a main face of a substrate, (2) forming a gate electrode on the 1st conductor, (3) removing the surface of the 1st semiconductor by using the gate electrode as a mask, (4) forming high-concn. the 2nd semiconductor layer of the same cond. to the 1st by self alignment, (5) heating the substrate, (6) forming an elec. insulator film on a main face of the substrate, and (7) forming an ohmic electrode on the 2nd semiconductor layer. The resulted device shows small fluctuation of mutual conductance in the driving region.

IT Transistors
 (field-effect insulated-gate, with low strain,
 manuf. including self alignment of ohmic electrode for)
 IT 7440-56-4, Germanium, uses
 RL: USES (Uses)
 (ohmic electrode including, self-aligned bottom layer for,
 for low strain thin film transistor)
 RN 7440-56-4 HCAPLUS
 CN Germanium (7CI, 8CI, 9CI) (CA INDEX NAME)

Ge

L123 ANSWER 11 OF 21 HCAPLUS COPYRIGHT 2003 ACS on STN
 AN 1995:923801 HCAPLUS
 DN 124:16104
 TI B incorporation in Ge(001) grown by gas-source molecular-beam epitaxy from Ge₂H₆ and B₂H₆
 AU Lu, Q.; Bramblett, T. R.; Hasan, M.-A.; Lee, N.-E.; Greene, J. E.
 CS Materials Res. Lab., Univ. Illinois, Urbana, IL, 61801, USA
 SO Journal of Applied Physics (1995), 78(10), 6027-32
 CODEN: JAPPAU, ISSN: 0021-8979
 PB American Institute of Physics
 DT Journal
 LA English
 CC 66-3 (Surface Chemistry and Colloids)
 Section cross-reference(s): 75, 76
 AB SIMS was used to det. the concn. and depth distribution of B incorporated into Ge (001) 2.times.1 films grown on Ge (001) substrates by gas-source MBE using Ge₂H₆ and B₂H₆. The B concns. (CB = 3 .times. 10¹⁶-4 .times. 10¹⁹ cm⁻³) increase linearly with increasing flux ratio (JB₂H₆/JGe₂H₆ = 8.2 .times. 10⁻³-1.7) at const. film growth temp. (Ts = 300-400.degree.) and increase exponentially with 1/Ts at const. JB₂H₆/JGe₂H₆ ratio. The difference in the overall activation energies for B and Ge incorporation over this growth temp. range is 0.22 eV while B₂H₆ reactive sticking probabilities range from 8 .times. 10⁻⁴ at 300.degree. to 2 .times. 10⁻⁵ at 400.degree.. SIMS depth profiles from B modulation-doped samples and 2-dimensional .delta.-doped samples grown at Ts < 350.degree. were abrupt to within instrumental resolu. with no indication of surface segregation. Structural anal. by in situ RHEED combined with postdeposition high-resolu. plan-view and cross-sectional TEM showed that all films were high-quality single crystals with no evidence of dislocations or other extended defects. The B doping had no measurable effect on Ge deposition rates.
 IT 7440-56-4, Germanium, properties
 RL: PEP (Physical, engineering or chemical process); PRP (Properties); TEM (Technical or engineered material use); PROC (Process); USES (Uses)
 (SIMS depth profile study of B incorporation in Ge (001) grown by gas-source MBE from B₂H₆ and Ge₂H₆)

123 ANSWER 7 OF 21 HCAPLUS COPYRIGHT 2003 ACS ON STN
 AN 2001.630924 HCAPLUS
 DN 135:188773
 TI Gate stack structure for variable threshold voltage
 IN Yu, Bin; Adem, Ercan
 PA Advanced Micro Devices, Inc., USA
 SO U.S., 25 PP
 CODEN: USXXAM
 DT Patent
 LA English
 IC ICM H01L031-119
 NCL 257407000
 CC 76-3 (Electric Phenomena)
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
FI	US 6281559	B1	20010828	US 1999-261274	19990303
PRAT	US 1999-261274		19990303		

AB An ultra-large-scale integrated (ULSI) circuit includes MOSFETs which have different threshold voltages and yet have the same channel characteristics. The MOSFETs include gate structures or gate stacks with a Si and Ge material provided over a seed layer. The seed layer can be a 20-40 ÅNG polysilicon layer. An amorphous Si layer is provided over the Si and Ge material, and a cap layer is provided over the amorphous Si layer. The polysilicon material is implanted with lower concns. of Ge, where lower threshold voltage MOSFETs are required. Over a range of 0-60 concn. of Ge, the threshold voltage can be varied by roughly 240 mV.
 RL: DEV (Device component use); PEP (Physical, engineering or chemical process); PROC (Process); USES (Uses)
 (CVD; silicon germanium compd. semiconductor gate stack structure for variable threshold voltage in ULSI circuits)

IT 7440-42-8, Boron, uses
 RL: MCA (Modifier or additive use); USES (Uses)
 (ion implanting; silicon germanium compd. semiconductor gate stack structure for variable threshold voltage in ULSI circuits)

IT 7440-56-4, Germanium, processes
 RL: DEV (Device component use); PEP (Physical, engineering or chemical process); PROC (Process); USES (Uses)
 (silicon germanium compd. semiconductor gate stack structure for variable threshold voltage in ULSI circuits)

L114 ANSWER 4 OF 4 HCAPLUS COPYRIGHT 2003 ACS on STN
 AN 1970:94467 HCAPLUS
 DN 72 94467
 TI Anomalous thermal behavior of boron-doped low-temperature germanium
 epitaxial layers
 AU Berkenblit, M.; Light, T. B.; Reisman, A.
 CS Watson Res. Center, IBM, Yorktown Heights, NY, USA
 SO Journal of the Electrochemical Society (1970), 117(3), 359-62
 CODEN: JESQAN, ISSN: 0013-4651
 DT Journal
 LA English
 CC 71 (Electric Phenomena)
 AB Recently, conditions have been defined for the growth of mirror-smooth
 layers of Ge on either Ge or semi-insulating Ga-As by the GeI2
 disproportionation reaction. In attempting to dope such layers with
 p-type impurities under the defined surface-rate-limited growth
 conditions, order-of-magnitude decreases in resistivity occurred on
 heating the grown layers to temps. higher than the original growth temp.
 This indicated that impurities were initially incorporated in an elec.
 inactive state. Results are presented which show this behavior to be
 increasingly pronounced for fast growth rates and low substrate temps.,
 and growth conditions to minimize the effect are defined.
 ST boron doped Ge; germanium B doped; exitaxial
 Ge layers

L103 ANSWER 22 OF 24 HCAPLUS COPYRIGHT 2003 ACS on STN

AN 1984.64472 HCAPLUS

DN 101.64472

TI Thin-film transistors

IN Nakagiri, Takashi; Hirai, Yutaka; Osada, Yoshiyuki

PA Canon K. K., Japan

SO Ger. Offen., 46 pp.

CODEN GWXXBX

DT Patent

LA German

IC H01L029-04; H01L029-78; H01L031-02; G09F009-35; G02F001-015

CC 76-3 (Electric Phenomena)

FAN CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 3331601	A1	19840308	DE 1983-3331601	19830901
	DE 3331601	C2	19870430		
	JP 59043575	A2	19840310	JP 1982-153105	19820902
	JP 59124163	A2	19840718	JP 1982-231521	19821229
	US 4740829	A	19880426	US 1986-937432	19861203

PRAI JP 1982-153105 19820902

JP 1982-231521 19821229

US 1983-527385 19830829

AB A stable and highly conductive thin-film transistor is fabricated with a polycryst. Ge or Ge-Si film contg. .ltoreq.3 at. % H. Thus, a Corning Glass no. 7059 washed with an HF-HNO3-HOAc soln., there was coated 1st a Ge-O.3 at. % H film at 400 degree. from a glow discharge in a gas mixt. of GeH4-H2-B2H6, a similar Ge film from a GeH4-H2-PH3 mixt., a SiNH film from a SiH4-H2-NH3 mixt., and after pattern etching, with Al contacts to form an FET.

IT Transistors
(field-effect, thin-film, fabrication of with polycryst.
germanium and silicon films contg. hydrogen)

L121 ANSWER 6 OF 8 HCAPLUS COPYRIGHT 2003 ACS on STN
 AN 1998:545517 HCAPLUS
 EN 129:238624
 TI Semiconductor device.
 IN Yamazaki, Shunpei
 PA Semiconductor Energy Laboratory Co., Ltd. (SEL), Japan
 SO Jpn. Kokai Tokkyo Koho, 10 pp.
 CODEV: JKKXAF
 DT Patent
 LA Japanese
 IC ICM H01L029-786
 ICS H01L029-78
 CC 76-3 (Electric Phenomena)
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 10223909	A2	19980821	JP 1997-40089	19970208
PRAI	JP 1997-40089		19970208		
AB	A semiconductor device such as a TFT comprises a gate electrode such as Al, polysilicon, or W silicide formed on a gate insulator film via material such as W, Ti, or Ge having a work function different from that of the gate electrode to control its threshold values.				
IT	7440-21-3, Silicon, uses RL: DEV (Device component use); USES (Uses) (polycryst.; gate electrode of semiconductor device)				
IT	7440-56-4, Germanium, uses RL: DEV (Device component use); USES (Uses) (gate electrode of semiconductor device)				
RN	7440-56-4 HCAPLUS				
CN	Germanium (7CI, 8CI, 9CI) (CA INDEX NAME)				

Ge

L123 ANSWER 17 OF 21 HCAPLUS COPYRIGHT 2003 ACS on STN
 AN 1989:86367 HCAPLUS
 DN 110:86367
 TI Epitaxial growth and band bending of n- and p-type
 germanium on gallium arsenide (001)
 AU Chambers, S. A.; Irwin, T. J.
 CS Mater. Dev. Lab., Boeing Electron. High Technol. Cent., Seattle, WA,
 98124-6269, USA
 SO Physical Review B: Condensed Matter and Materials Physics (1988), 38(11),
 7484-92
 CODEN: PRBMDO; ISSN: 0163-1829
 DT Journal
 LA English
 CC 76-2 (Electric Phenomena)
 Section cross-reference(s): 66, 73
 AB High-resoln. XPS, LEED, and x-ray photoelectron diffraction were combined
 to examine the interface structure and band-bending characteristics of n-
 and p-type Ge epilayers grown on semi-
 insulating GaAs(001). The 1st monolayer of Ge intermixes with
 atoms in the near-surface region to yield a complex structure. Subsequent
 Ge monolayers grow epitaxially but exhibit surface roughness in the form
 of local variation in layer thickness of the order of 2-3 monolayers (3-4
 .ANG.), in agreement with previous RHEED measurements obtained during
 continuous overlayer growth. The growth of undoped (which is actually
 p-type) and As-doped Ge
 overlayers results in Schottky-barrier-height changes of +0.05 and
 -0.35 eV, resp., relative to the clean-surface value of 0.83 +/- 0.05 eV.
 The barrier height correlates directly with dopant level in the Ge
 epilayer. In contrast, the valence band offset is independent of dopant
 level in the Ge film and maintains a const. value of
 0.60 +/- 0.05 eV. With the exception of the barrier height of the
 starting surface, these results are the same as those obtained on n-type
 substrates, further supporting the conclusion that barrier-height
 formation and band-offset development occur independently.

1.42 ANSWER 23 OF 29 WPIX COPYRIGHT 2003 THOMSON DERWENT on STN
 AN 1992-131697 [16] WPIX
 CR 1993-328086 [41]
 DNN N1992-098226 DNC C1992-061652
 TI **Germanium silicon di oxide gate MOSFET** - comprises
 doped silicon substrate with silica gate and thin film of poly- silicon on
 gate oxide.
 AW METAL OXIDE SEMICONDUCTOR FIELD EFFECT TRANSISTOR.
 DC L03 U11 U12
 IN OZTURK, M, WORTMAN, J
 PA (UYNC-N) NORTH CAROLINA S UN
 CYC 1
 PI US 5101247 A 19920331 (199216)* 6p
 ADT US 5101247 A US 1990-515595 19900427
 PRAI US 1990-515595 19900427
 IC H01L029-10
 AB US 5101247 A UPAB: 19931130
 A MOSFET, with a silica/poly-Si/Ge gate, formable at
 high throughput using little heat and using self-alignment, comprises a
 doped Si substrate (21) on which is a silica gate (22) with oppositely
 doped adjacent to source (23) and drain (24) forming pn junctions with the
 gate, and a thin film of poly-Si (25) on the gate oxide. This is thick
 enough to support a thin film Ge gate contact (26)
 which is then deposited upon it.
 Pref. the poly-Si film is only 10 (or 5) nm thick and pref. the Si
 substrate is a wafer comprising locally oxidised Si to isolate the
 transistor. Pref. there is an insulating passivating layer on source,
 drain and gate having openings for contacts. Pref. the Ge
 film is polycrystalline.
 USE/ADVANTAGE - A MOSFET having a silica/poly-Si/Ge
 gate structure (claimed) is provided which may be mfd. at high
 throughput with a lower thermal budget. The high temps. and low rates in
 poly-Si deposition are less of an obstacle since only a thin layer is
 needed to support the Ge, which is deposited at 350 deg.C by LPCVD.
 32/2
 Dwg. 32/2
 FS CPI EPI
 FA AB, GI